## Amendments to the claims:

The listing of claims set forth below replace all prior versions in the listings of claims in the subject application:

## In the Claims:

Claim 1 (Currently Amended) An abrasive composition for polishing substrates comprising:

a plurality of colloidal silica abrasive particles comprising a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 2 (Currently Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 15% by volume of the abrasive particles.

Claim 3 (Currently Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 10% by volume of the abrasive particles.

Claim 4 (Currently Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size

distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 15% by volume of the abrasive particles.

Claim 5 (Currently Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 6 (Currently Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 7 (Currently Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 8 (Canceled).

Claim 9 (Canceled).

Claim 10 (Canceled).

Claim 11 (Currently Amended) An abrasive slurry composition for polishing substrates comprising:

a plurality of colloidal silica abrasive particles comprising a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, and a span value, <u>by volume</u>, being greater than or equal to 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles; and

a solution having one or more chemical reactants.

Claim 12 (Currently Amended) An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 10% by volume of the abrasive particles.

Claim 13 (Currently Amended) An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 14 (Currently Amended) An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about

100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 15 (Canceled).

Claim 16 (Canceled).

Claim 17 (Currently Amended) A method for polishing substrates with an abrasive composition comprising:

providing a substrate to be polished;

and polishing the substrate using a plurality of colloidal silica abrasive particles comprising, a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 20 nanometers, and wherein a fraction of said particles greater than about 100

nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 18 (Currently Amended) A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 10% by volume of the abrasive particles.

Claim 19 (Currently Amended) A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 20 (Currently Amended) A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, <u>by volume</u>, being about 20 nanometers to about 100 nanometers, a span value, <u>by volume</u>, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

Claim 21 (Canceled).

Claim 22 (Canceled).